



INFORMATION DISCLOSURE CITATION FORM FOR PATENT APPLICATION (FORM PTO-1449) (Substitute)	Docket No.: YOR920030339US1	Serial No.: 10/727,901
	Applicant(s): Alan Edward Rosenbluth	
	Filing Date: 12/4/2003	Group: 2851

U.S. PATENT DOCUMENTS

Examiner Initials	Document Number (Number-Kind Code)	Publication Date (MM-DD-YYYY)	Name of Patentee or Applicant	Class	Sub-class
J K	US-5,680,588	10-21-1997	Gortych et al.	395	500
	US-6,563,566 B2	05-13-2003	Rosenbluth et al.	355	67
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				
	US-				

FOREIGN PATENT DOCUMENTS

Examiner Initials	Document Number (Country Code-Number-Kind Code)	Publication Date (MM-DD-YYYY)	Name Of Patentee of Applicant	Translation? Yes/No/n/a
J K	- -			
	- -			
	- -			
	- -			
	- -			
	- -			

OTHER DOCUMENTS (Author (Capitalize), Title, Date, Pages, Etc., if known)

J	M. Burkhardt, et al., "Illuminator design for the printing of regular contact patterns," Microelectronic Engineering 41-42 (1998); p. 91
	T.-S. Gau, et al., "The Customized Illumination Aperture Filter for Low k1 Photolithograph Process," SPIE v. 4000 - Optical Microlithography XIII, (2000): p. 271
	A. E. Rosenbluth, et al., "Optimum Mask and Source Patterns to Print a Given Shape," Journal of Microlithography, Microfabrication, and Microsystems v.1, no. 1 (2002): P. 13
	R. Socha, et al., "Illumination optimization of periodic patterns for maximum process window," Microelectronic Engineering 61-62 (2002): p. 57
	A. K. Wong, et al., "Level-specific lithograph optimization for 1-Gb DRAM," IEEE Transactions on Semiconductor Manufacturing 13, no. 1 (Feb. 2000): p. 76
	M. Born et al., Principles of Optics, 5 ed. (Oxford: Pergamon, 1975)

Examiner's Signature: <i>Alan Rosenbluth</i>	Date Considered: <i>7-14-03</i>
Initial if reference was considered, whether or not citation is in conformance with MPEP. Mark through citation if not considered. Include a copy of this citation form with your next correspondence to the Applicant(s).	